Composition for polishing surfaces of silicon dioxide

Abstract

A composition for polishing surfaces comprises the following components:

a) at least one inorganic abrasive component (S) comprising a lanthanide oxide,

b) at least one organic dispersing-agent component based on polymer (P),

c) at least one organic gelling agent (G) such as gellan gum,

d) water as solution or dispersing medium, and

e) if appropriate further auxiliary and additive materials

and has high stability.